

DOCKET: FI9-97-288

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

INVENTOR: Christopher Obszarny ) EXAMINER: P. Kim  
SERIAL NO.: 09/116,395 ) ART UNIT: 2851  
FILING DATE: July 16, 1998 ) DATE:  
FOR: Apparatus and Method )  
for In-Situ Adjustment of )  
light Transmission in a )  
Photolithography Process )

**AMENDMENT UNDER RULE 312**

Assistant Commissioner of Patents  
Washington, D.C. 20231

Dear Sir:

Responsive to the Notice of Allowance dated July 20, 2000, please amend the application as follows:

**In the Specification**

On page 5, line 2, delete "photo-mask" and substitute therefor -- photo mask --.

On page 5, line 4, delete "Matsumoto's" and substitute therefor -- Matsumoto --.

On page 5, line 19, delete "photo lithographic" and substitute therefor  
-- photolithographic --.

On page 8, line 3, after "by" delete "the".

On page 10, line 4, delete "cross section" and substitute therefor -- cross-section --.

On page 10, line 8, delete "cross section" and substitute therefor -- cross-section --.

**REMARKS**

Applicant notes with appreciation the allowance of this case in the Notice of Allowance mailed on July 20, 2000. In the course of preparing the application for grant,

RECEIVED  
AUG 15 2000  
PRODUCTION CONTROL  
PUBLISHING DIVISION